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## Electronic Supplementary Information

# 5.1% efficiency of Si photoanode for photoelectrochemical water splitting catalyzed by porous NiFe (oxy)hydroxide converted from NiFe oxysulfide

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## **Experimental section**

### **The fabrication of n<sup>+</sup>pp<sup>+</sup>-Si electrodes**

Single-crystalline p-Si wafers (156×156×0.18 mm<sup>3</sup>, 1–3 Ω• cm specific resistance) were used in this work. The pyramid surface texture on both sides of silicon wafers was produced by chemical etching in a solution of KOH (Sigma, reagent grade) on a mass production line of crystalline-Si solar cells in the Suzhou company of Canadian Solar Inc. The as-prepared p-Si wafers were first covered with liquid phosphorus and boron dopant precursor by spin coating, respectively. Subsequently, to form an n<sup>+</sup> emitter layer and a p<sup>+</sup> electron back reflection layer for the p-Si, a thermal diffusion process was conducted at 950 °C for 180 min under the atmosphere of nitrogen in a diffusion furnace. After doping, an anti-reflection SiN<sub>x</sub> layer and fritted Ag rod line were produced onto the n<sup>+</sup>-Si emitter side. Finally, the samples were laser-cut into 1.5×1.5 cm<sup>2</sup>. Such electrodes were then rinsed in deionized water which was degassed by ultrasonic clearing machine (i-Quip, Aladdin) and dried under a stream of N<sub>2</sub>. We called such photoanode as n<sup>+</sup>pp<sup>+</sup>-Si. During PEC reaction, the light will be entering from n<sup>+</sup> side which was sealed on a transparent quartz substrate. The p<sup>+</sup> side will be loaded with the Ni protective layer and the NiFe related catalyst.

### **E-beam evaporation of the Ni layer on the Si surface**

Before use, Si electrodes were cleaned by subsequent sonication in acetone, ethanol and water for 15 minutes each to remove any contaminants. The native SiO<sub>2</sub> layer on the p<sup>+</sup> side was then etched by dropping 5 wt % HF solution. A Ni layer was deposited on the Si surface via e-beam evaporation at a deposition rate of 0.5 Å s<sup>-1</sup>. A layer thickness of ~10 nm was controlled and measured using the transmission electron microscope (TEM). Then, this Ni layer was partially activated in a three electrode PEC system to form a thin NiO<sub>x</sub> layer on its surface. We called such electrode as n<sup>+</sup>pp<sup>+</sup>-Si/Ni/NiO<sub>x</sub>. In detail, the Si/Ni electrode was activated by cycling the potential between 0.6 to 1.8 V<sub>RHE</sub> using the cyclic voltammetry measurement for five times on the electrochemical workstation in 1.0 M NaOH electrolyte at the sweep rate of 5 mV/s

under simulated solar light (100mW/cm<sup>2</sup>), with a Pt sheet as a counter electrode, Ag/AgCl (3M KCl) as a reference electrode and the n<sup>+</sup>pp<sup>+</sup>-Si/Ni as a working electrode.

### **Electrodeposition of the catalysts**

The NiFe-S catalyst was electrodeposited on n<sup>+</sup>pp<sup>+</sup>-Si/Ni/NiO<sub>x</sub> using the Ni layer as the working electrode, Pt wire as a counter electrode and Ag/AgCl (3M KCl) as a reference electrode. The deposition solution contains 5 mM NiSO<sub>4</sub>, 1 mM FeSO<sub>4</sub> and 0.5 M thiourea in water. The potential of consecutive linear scan was cycled between -0.2 and 0.8 V<sub>RHE</sub> at a scan rate of 5 mV/s under stirring. After deposition, the electrode was rinsed with copious water gently and dried under vacuum at room temperature overnight. This electrode was defined as n<sup>+</sup>pp<sup>+</sup>-Si/Ni/NiO<sub>x</sub>/NiFe-S.

Then, we subjected the Si/Ni/NiO<sub>x</sub>/NiFe-S to PEC measurements for ten times by cyclic voltammetry between 0.6 and 1.8 V<sub>RHE</sub> under AM1.5G 1 sun illumination and 1M NaOH. The electrode was again rinsed with copious water gently and dried under vacuum at room temperature overnight. This electrode was defined as n<sup>+</sup>pp<sup>+</sup>-Si/Ni/NiO<sub>x</sub>/NiFe-C. To make a comparison with the traditional NiFe (oxy)hydroxide, we also electrodeposited such catalyst using the same condition as that of NiFe-S except for the adding of thiourea in the deposition solution. After the deposition, the sample was also subjected to PEC measurements for ten times. This electrode was called as n<sup>+</sup>pp<sup>+</sup>-Si/Ni/NiO<sub>x</sub>/NiFe.

### **PEC measurements**

PEC measurements were conducted in a three-electrode cell configuration, using the Si photoanode as the working electrode, Ag/AgCl (3M KCl) as the reference electrode, and a Pt wire as the counter electrode. The potentials were controlled using an electrochemical workstation (Vertex, Ivium Technologies) and re-scaled to the potential according to the following equation:  $V_{RHE} = V_{Ag/AgCl} + 0.197 \text{ V} + \text{pH} \times 0.059 \text{ V}$ . A 300 W Xe lamp (Oriel, Newport Co.) with a silica filter to simulate solar light (AM1.5G illumination) was used as the light source. Before the PEC measurement, the

light intensity was carefully controlled at 100 mW/cm<sup>2</sup>, measured using an optical power meter (Newport company) just before the light enters into the PEC cell. The performance of the photocathodes was measured using linear sweep voltammograms (LSVs) at 5 mV/s in a solution containing 1 M NaOH.

The solar-to-oxygen conversion efficiency ( $\eta$ ) of a photoanode can be calculated based on the PEC current-potential curve like that of a solar cell, using equation:  $\eta = J_{mp} (1.23 V_{RHE} - V_{mp}) / P_{in}$ , with  $J_{mp}$  and  $V_{mp}$  ( $V_{RHE}$ ) are the photocurrent and potential at the maximum power point, respectively, and  $P_{in}$  as the power density of the illumination. It is assumed that there is no corrosion reaction at the photoelectrode, and a Faradaic efficiency of unity for both reactions.

To measure the stability of the photoelectrode, potential vs. time measurements were conducted at a constant current density of 40 mA/cm<sup>2</sup> for OER in 1 M NaOH solution under simulated AM1.5G illumination. The electrolyte was replaced and the sample was rinsed every 24h during the stability measurements.

The electrochemical impedance spectroscopy (EIS) curves were obtained at a constant 1.0  $V_{RHE}$  using an electrochemical workstation (Vertex, Ivium Technologies) in the frequency range from 1 Hz to 100 MHz under illumination.

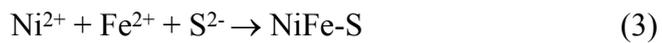
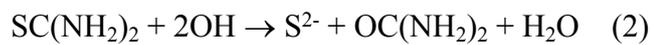
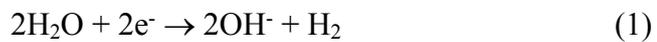
The Faradaic efficiency of the illuminated photoanodes was determined in a manner similar to the photocurrent measurements at a constant potential of 1.0  $V_{RHE}$  and the amount of hydrogen produced on the Pt electrode was obtained using a gas chromatograph equipped with a thermal conductivity detector (Tianmei, GC 7900T).

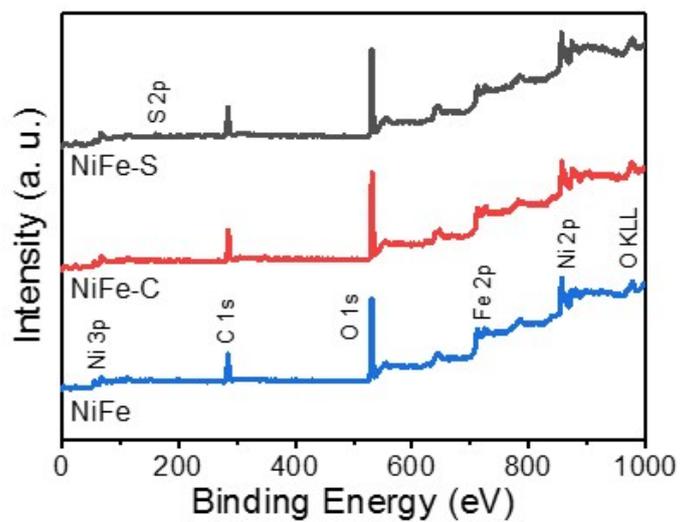
### **Materials characterization**

The surface morphology of the sample surface was analyzed using a field-emission scanning electron microscope (SEM) (SU8010, Hitachi). Transmission electron microscope (TEM) analysis was conducted by a Tecnai G220 (S-TWIN, FEI) operating at 200 kV. X-ray photoelectron spectroscopy (XPS) measurements were performed at room temperature using a spectrometer hemispherical analyzer (ESCALAB 250Xi, Thermo). All the binding energies were referenced to adventitious carbon at 284.6 eV.

### **The mechanism of the electrodeposition of NiFe-S.**

Similar to the electrodeposition of Ni-Co-S (ACS Appl. Mater. Interfaces 2017, 9, 19746–19755), we proposed the overall reactions involved in the deposition of the NiFe-S catalyst are given below:

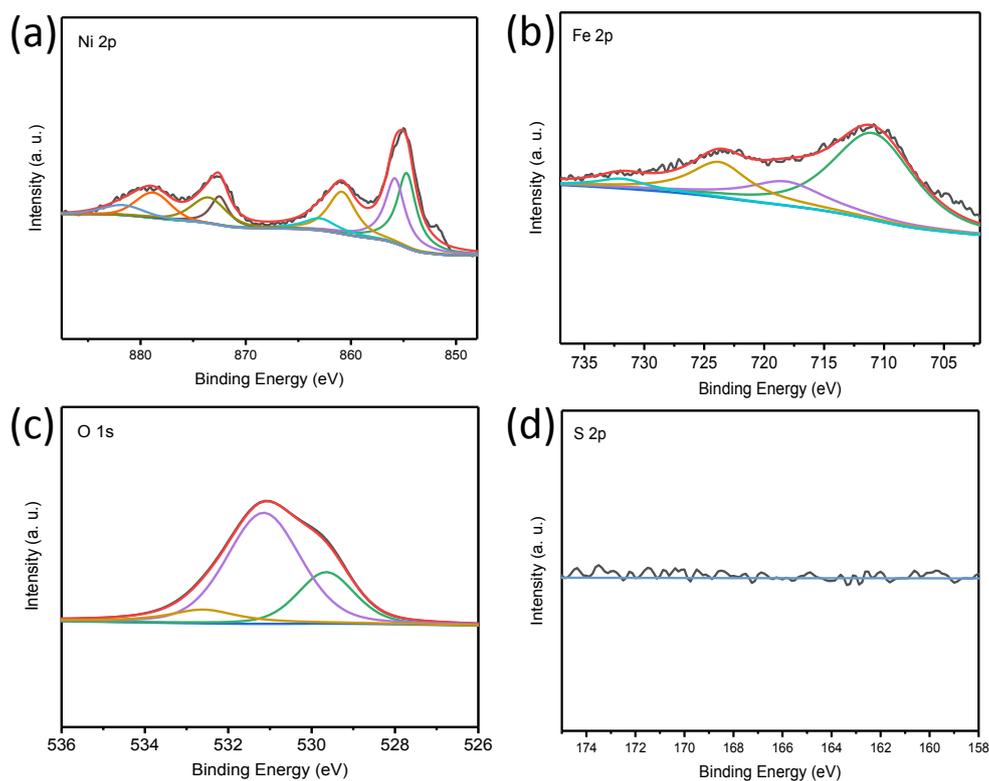




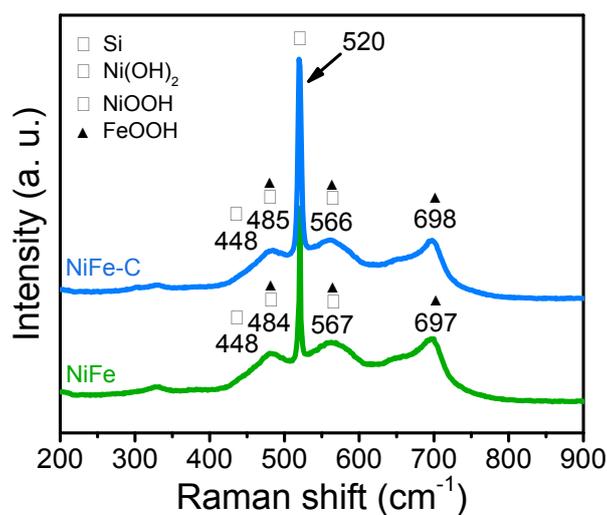
**Fig. S1** Full XPS spectra of the NiFe, NiFe-C and NiFe-S deposited on  $n^{+}pp^{+}Si/Ni/NiO_x$ .

**Table S1** Quantitative ratios of  $Ni^{2+}$  and  $Ni^{3+}$  in the NiFe and NiFe-C samples.

Core Level	Sample	Quantitative Ratios (%)	
		$Ni^{3+}$ (%)	$Ni^{2+}$ (%)
$Ni\ 2p_{1/2}$	NiFe	44.54	55.46
	NiFe-C	52.02	47.98
$Ni\ 2p_{3/2}$	NiFe	47.37	52.63
	NiFe-C	54.70	45.30

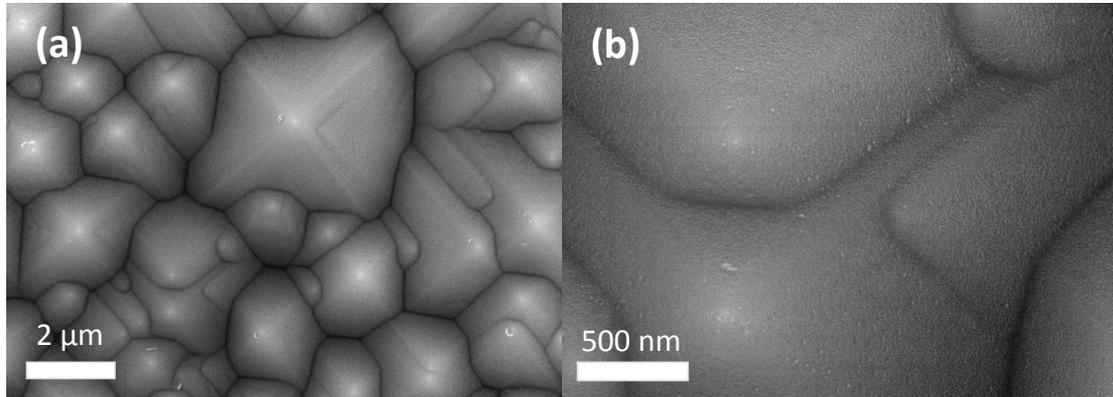


**Fig. S2** High-resolution XPS spectra of (a) Ni 2p, (b) Fe 2p, (c) O 1s and (d) S 2p in Si/Ni/NiO<sub>x</sub>/NiFe-C after etched ~10 nm on the electrode surface. There is also no S element inside the sample.

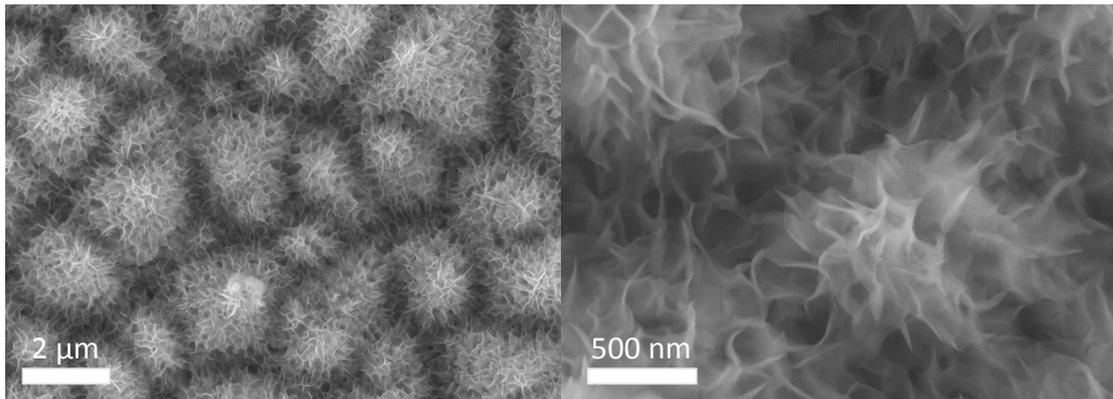


**Fig. S3** Raman spectra for Si/Ni/NiO<sub>x</sub>/NiFe and Si/Ni/NiO<sub>x</sub>/NiFe-C. No significance

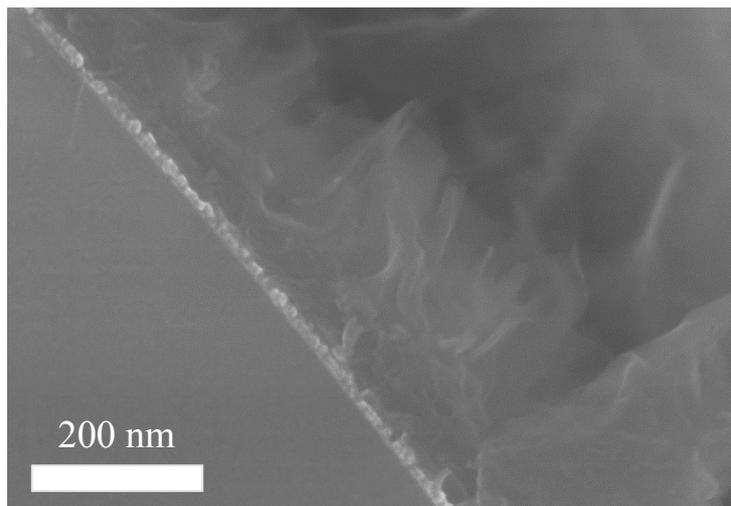
changes were found. The peak at  $448\text{ cm}^{-1}$  is assigned to  $\text{Ni}(\text{OH})_2$ , the peaks at around  $486\text{ cm}^{-1}$  and  $566\text{ cm}^{-1}$  are both attributed to  $\text{NiOOH}$  and  $\text{FeOOH}$  and the peak at  $698\text{ cm}^{-1}$  is attributed to  $\text{FeOOH}$ .



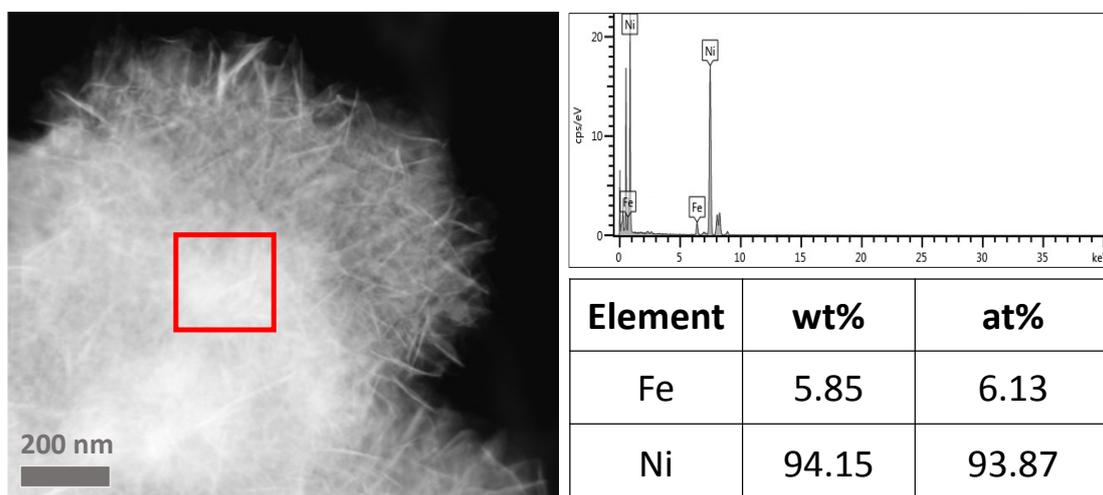
**Fig. S4** The SEM images of  $\text{Si}/\text{Ni}/\text{NiO}_x$  on the MP textured Si surface. The Ni layer deposited via e-beam evaporation is quite dense and smooth.



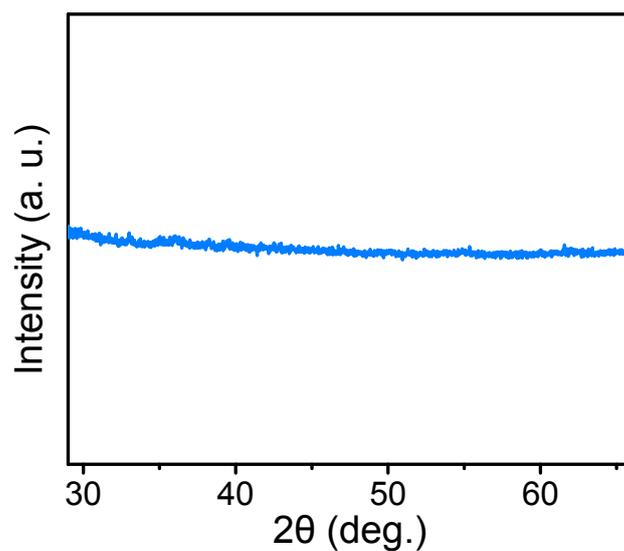
**Fig. S5** The SEM surface images of  $\text{Si}/\text{Ni}/\text{NiO}_x/\text{NiFe-S}$ . Right picture is the enlarged one.



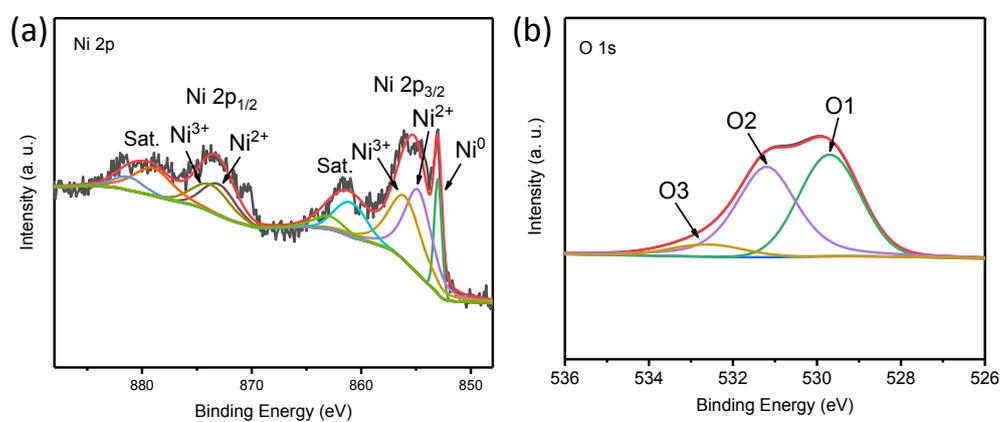
**Fig. S6** The enlarged view from Fig. 2c.



**Fig. S7** The Energy Dispersive X-Ray Spectroscopy (EDS) results for NiFe-C. The mole ratio of Fe/Ni is determined to be 6.5%.



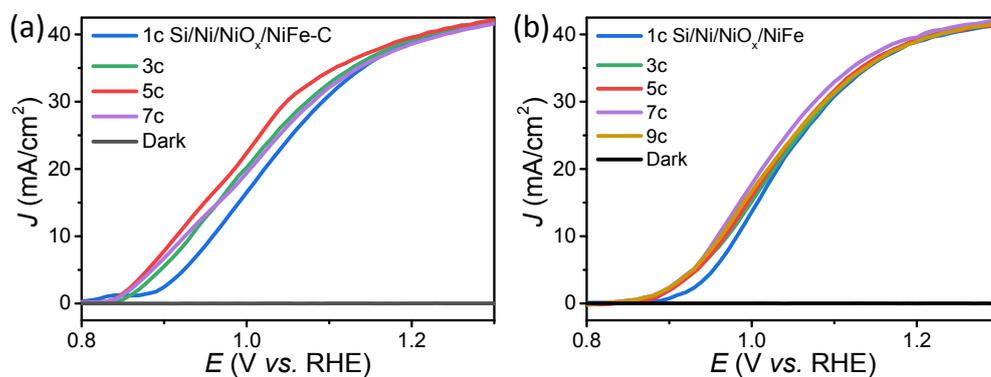
**Fig. S8** X-ray diffraction (XRD) spectrum of NiFe-C. No diffraction peaks were observed in the XRD spectrum, suggesting the poor crystallinity of the catalysts.



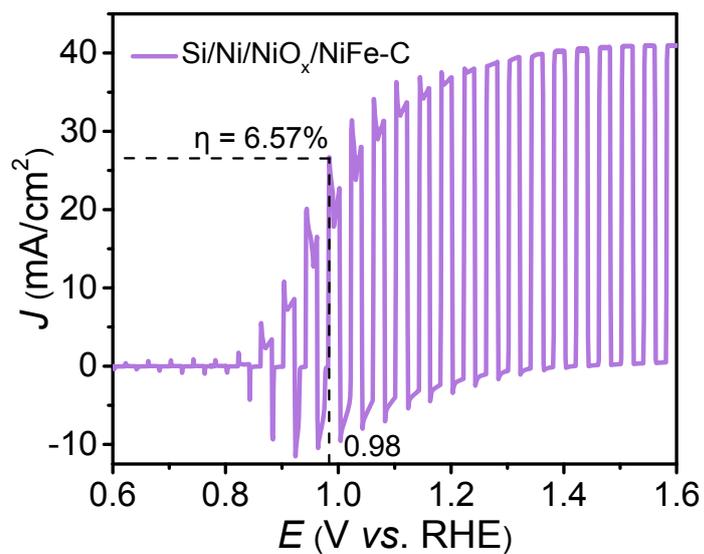
**Fig. S9** High-resolution XPS spectra of (a) Ni 2p and (b) O 1s on the Si/Ni/NiO<sub>x</sub> surface, showing the formation of NiO<sub>x</sub>.



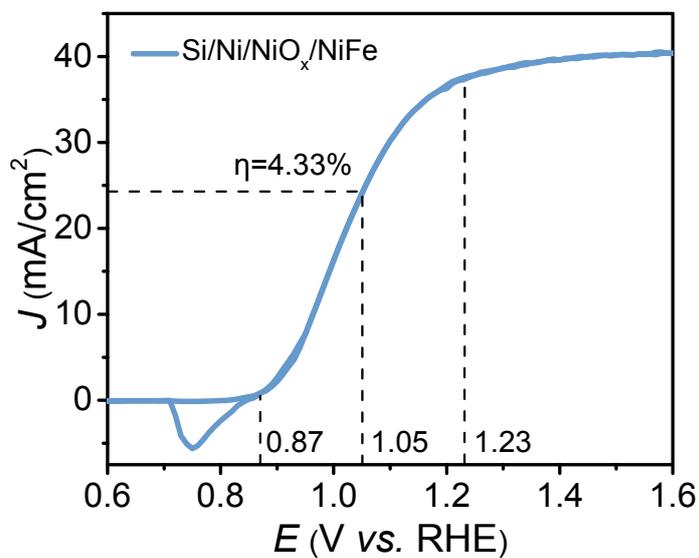
**Fig. S10** EDS elemental mapping of element S for Si/Ni/NiO<sub>x</sub>/NiFe-C.



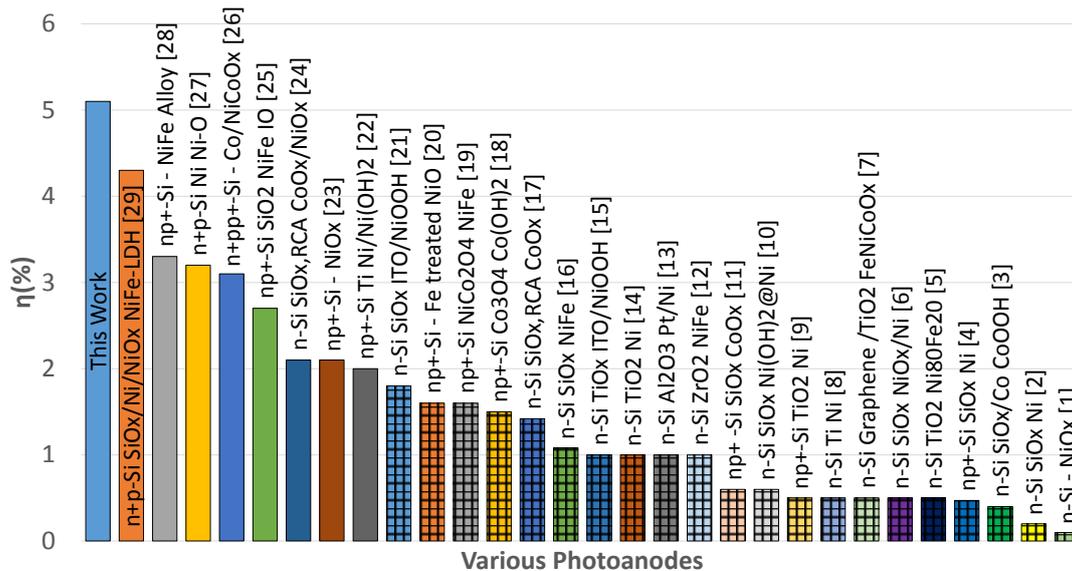
**Fig. S11** (a) PEC  $J$ - $V$  curves of Si/Ni/NiO<sub>x</sub>/NiFe-C (a) and Si/Ni/NiO<sub>x</sub>/NiFe (b) with different deposition cycles. Si/Ni/NiO<sub>x</sub>/NiFe-C (5 cycles) shows the best PEC-OER activity, while that for Si/Ni/NiO<sub>x</sub>/NiFe is 7 cycles.



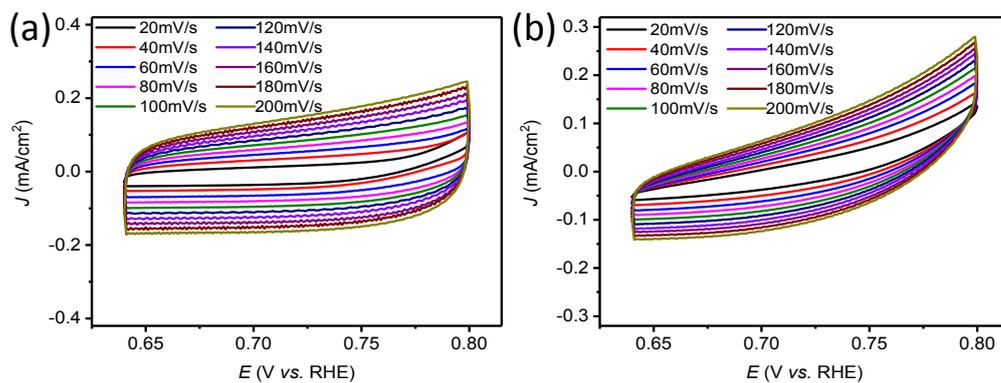
**Fig. S12** PEC J-V curve of NiFe-C under chopped illumination. Conversion efficiency  $\eta$  can reach up to 6.5%.



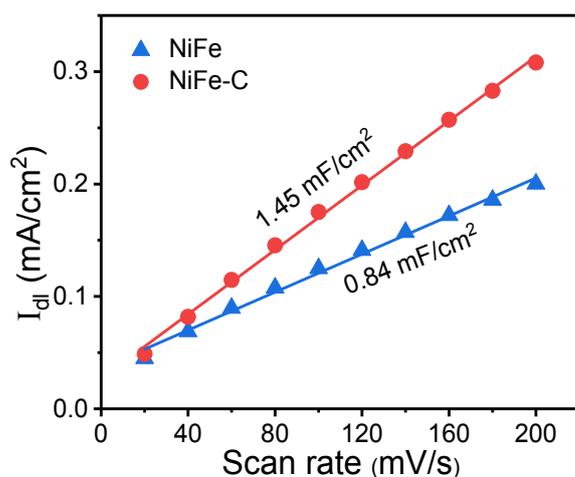
**Fig. S13** The PEC performance of Si/Ni/NiO<sub>x</sub>/NiFe photoanode. An onset potential of 0.87 V<sub>RHE</sub> and an energy conversion efficiency of 4.33% at 1.05 V<sub>RHE</sub> can be obtained.



**Fig. S14** Comparison of the energy conversion efficiency for the reported Si-based photoanodes with the current one.

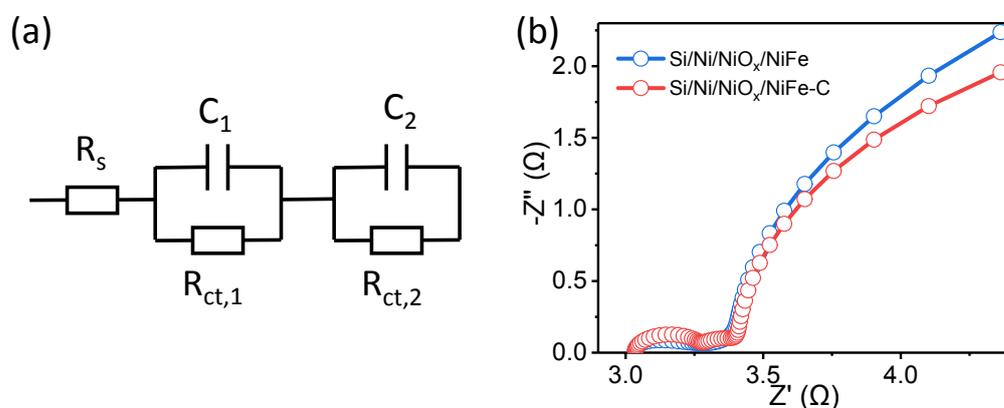


**Fig. S15** Typical CV curves of (a) Si/Ni/NiO<sub>x</sub>/NiFe-C and (b) Si/Ni/NiO<sub>x</sub>/NiFe.



**Fig. S16** Capacitive currents  $I_{dl}$  of Si/Ni/NiO<sub>x</sub>/NiFe-C and Si/Ni/NiO<sub>x</sub>/NiFe at 0.725 V<sub>RHE</sub> as a function of the scan rate.

Electrochemical capacitance was measured using cyclic voltammetry (CV) measurements in dark. The currents were measured in a narrow potential window (0.65-0.80 V<sub>RHE</sub>) that no faradaic processes were observed. CVs were collected at different scan rates: 20, 40, 60, 80, 100, 120, 140, 160, 180 and 200 mV/s. The measured current in this non-faradaic potential region should be mostly due to the charging of the double-layer. The capacitive current was the difference values between two currents at 0.725 V<sub>RHE</sub>.

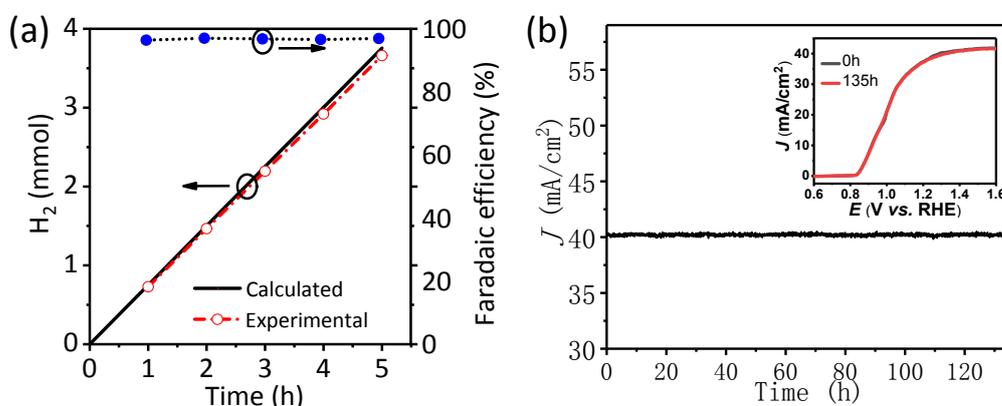


**Fig. S17** (a) Equivalent circuits for Si/Ni/NiO<sub>x</sub>/NiFe and Si/Ni/NiO<sub>x</sub>/NiFe-C and (b) the corresponding EIS Nyquist plots.

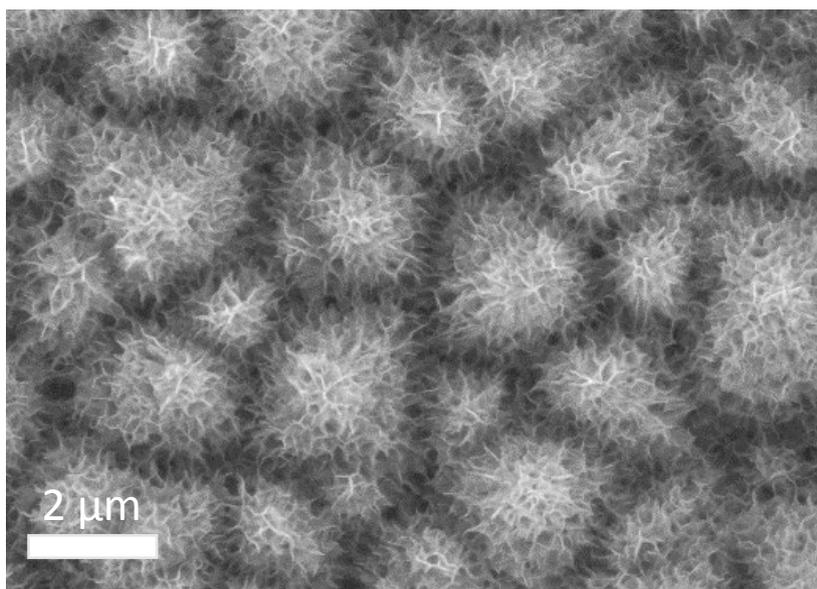
$R_s$  represents series resistance of the whole circuit.  $R_{ct,1}$  represents charge-transfer resistance from Si photoelectrode to catalyst and  $C_1$  is the capacitance of the corresponding Si photoelectrode/catalyst junction,  $R_{ct,2}$  represents the charge-transfer resistance from the NiFe or NiFe-C catalyst to the electrolyte and  $C_2$  is the capacitance of the corresponding catalyst/electrolyte junction.

**Table S2** Fitting EIS data for the NiFe-C and NiFe using the equivalent circuit.

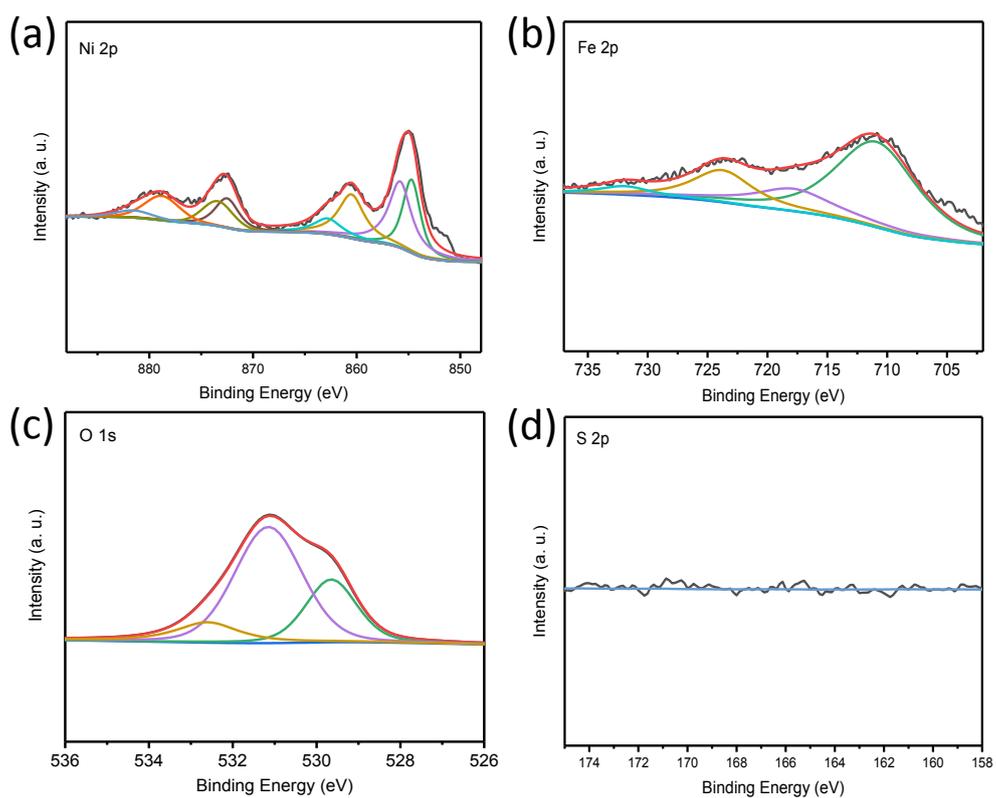
	NiFe-C	NiFe
$R_s(\Omega)$	3.056	3.551
$R_{ct,1}(\Omega)$	0.031	0.260
$R_{ct,2}(\Omega)$	4.803	5.999



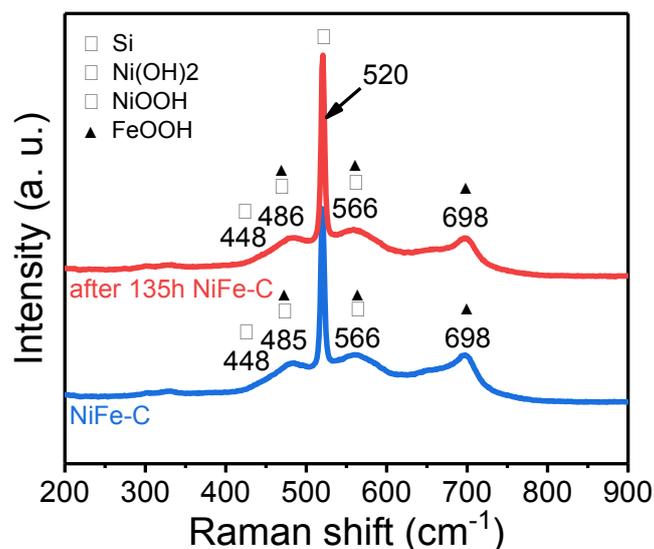
**Fig. S18** (a) H<sub>2</sub> production on time and the corresponding Faradic efficiency for Si/Ni/NiO<sub>x</sub>/NiFe-C. (b) PEC stability measurement for Si/Ni/NiO<sub>x</sub>/NiFe-C biased at 1.2 V<sub>RHE</sub> in 1M NaOH solution under 100 mW/cm<sup>2</sup> Xe lamp. The inset is the J-V curves before and after 135 h PEC reaction.



**Fig. S19** SEM surface morphology of Si/Ni/NiO<sub>x</sub>/NiFe-C after 135 h PEC reaction.



**Fig. S20** High-resolution XPS spectra of (a) Ni 2p, (b) Fe 2p and (c) O 1s, and (d) S 2p of Si/Ni/NiO<sub>x</sub>/NiFe-C after 135 h PEC reaction.



**Fig. S21** Raman spectra before and after the 135h testing for Si/Ni/NiO<sub>x</sub>/NiFe-C.

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